

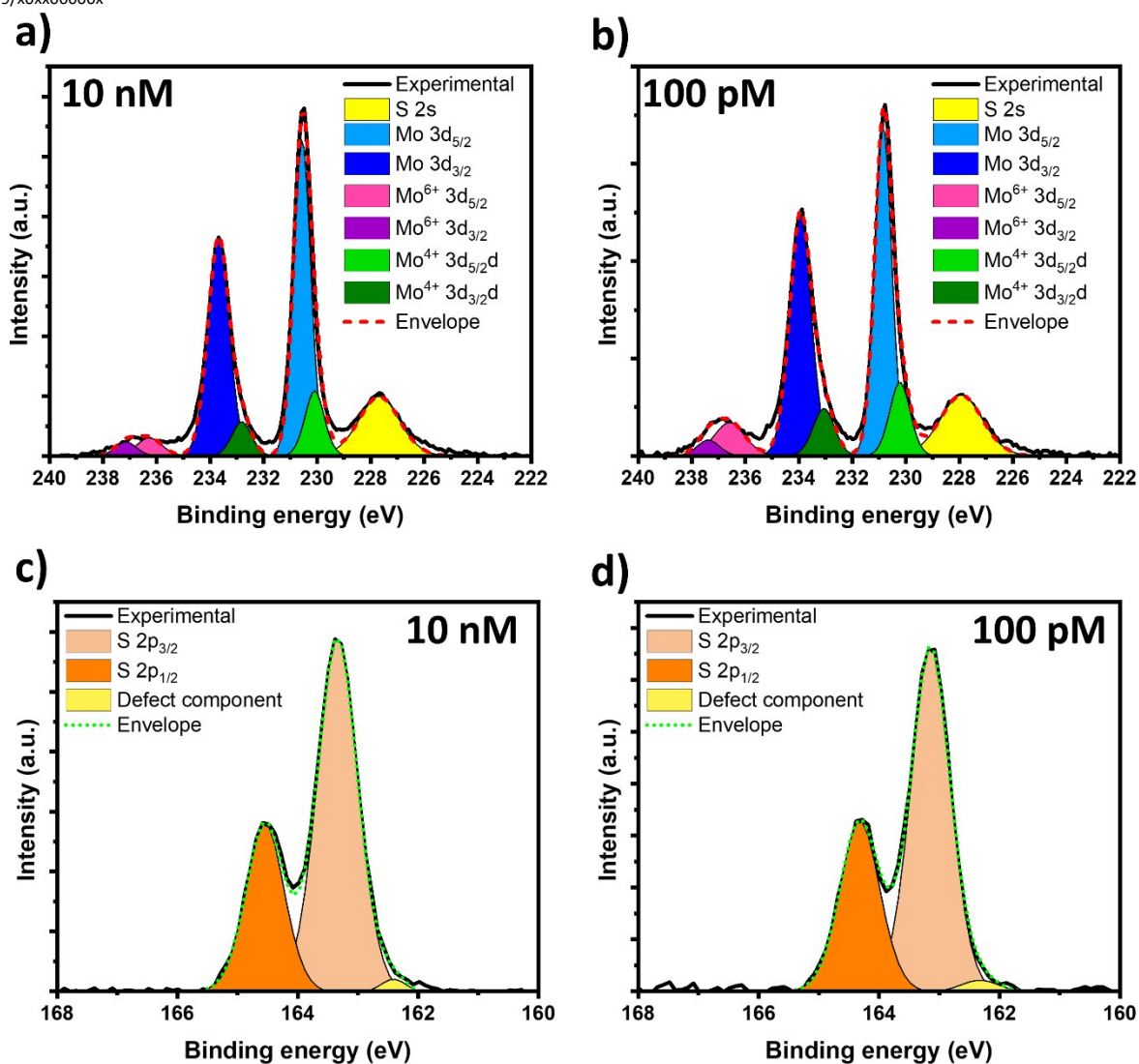
## Electronic Supplementary Information

### Field-Effect Transistors Based Ion Sensors: Ultrasensitive Mercury (II) Detection via Healing of MoS<sub>2</sub> Defects

Fernando J. Urbanos,<sup>a</sup> Sara Gullace<sup>a</sup> and Paolo Samorì <sup>\*a</sup>

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<sup>a</sup> University of Strasbourg CNRS, ISIS UMR 7006, 8 Allée Gaspard Monge,  
Strasbourg F-67000, France

\* E-mail: samori@unistra.fr

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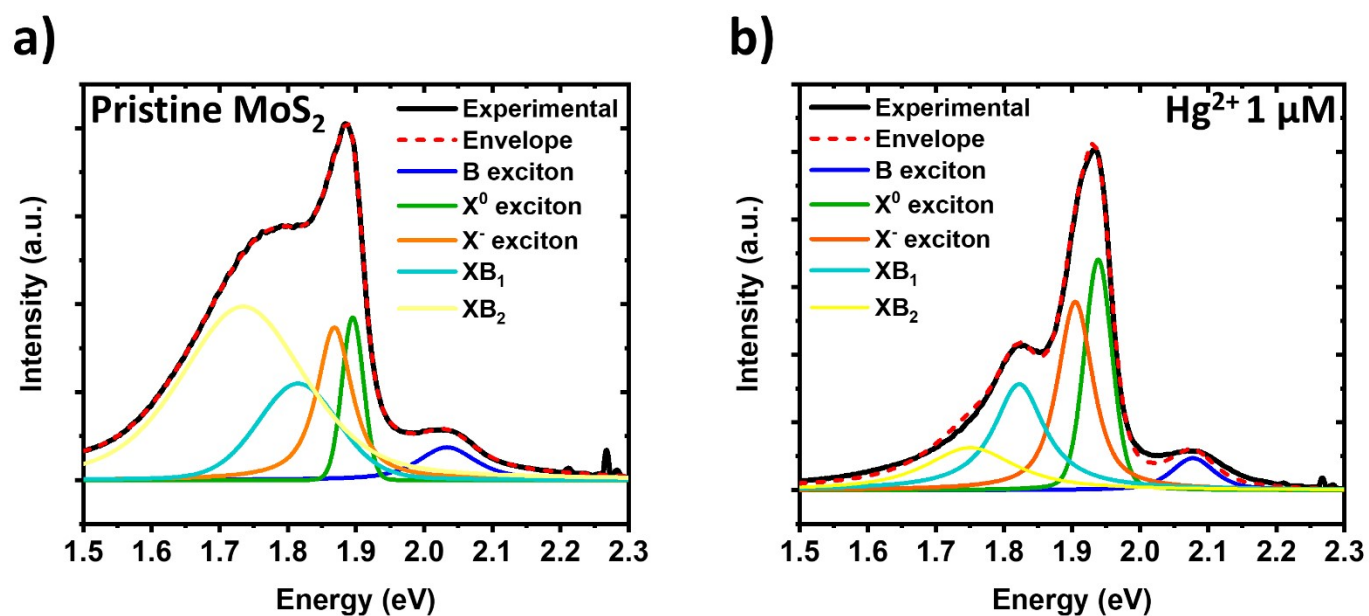
**Fig S1:** High-resolution XPS spectra of CVD MoS<sub>2</sub> exposed to different Hg<sup>2+</sup> concentrations. **a)** and **b)** Mo 3d XPS spectra at 10 nM and 100 pM, respectively. After deconvolution of the peaks, contribution coming from defective Mo<sup>4+</sup> is decreasing with increasing Hg<sup>2+</sup> concentration. **c)** and **d)** S 2p XPS spectra at 10 nM and 100 pM, respectively. Again, the defect component's intensity is decreasing with increasing concentration, indicating defect healing.

	Peak Contribution (%)			
	Control	100 pM	10 nM	1 μM
Mo 3d <sub>5/2</sub>	30.08	32.26	35.39	35.63
Mo 3d <sub>3/2</sub>	29.92	30.00	30.55	32.74
Mo <sup>6+</sup> 3d <sub>5/2</sub>	7.25	6.08	3.12	2.77
Mo <sup>6+</sup> 3d <sub>3/2</sub>	2.85	2.16	2.05	1.63
Mo <sup>4+</sup> def 3d <sub>5/2</sub>	9.38	8.73	8.36	7.63
Mo <sup>4+</sup> def 3d <sub>3/2</sub>	6.38	5.96	4.53	2.63
S 2s	13.88	14.82	15.99	16.97
S 2p <sub>1/2</sub>	31.15	31.97	30.45	31.49
S 2p <sub>3/2</sub>	62.42	65.99	67.68	67.24
Defects	6.43	2.45	1.67	1.27

**Table S1:** Peak contribution (in %) of every component after deconvolution of the high-resolution Mo 3d and S 2p XPS spectra as a function of different Hg<sup>2+</sup> concentrations. Mo<sup>4+</sup> defective component, associated to sulphur vacancies, and the so called “defects” decreased when increasing the Hg<sup>2+</sup> concentration, confirming defect healing.

	Peak Contribution (%)											
	Control			100 pM			10 nM			1 μM		
	M1	M2	M3	M4	M5	M6	M7	M8	M9	M10	M11	M12
S 2p def	6.43	6.99	6.06	2.45	3.48	2.87	1.67	1.76	1.76	1.27	1.56	1.41
Mean	6.49			2.93			1.73			1.41		
SD	0.47			0.52			0.05			0.15		

**Table S2:** Peak contribution (in %) of the defect related component after deconvolution of the high-resolution S 2p XPS spectra as a function of different Hg<sup>2+</sup> concentrations on a total of 12 points (M1-M12) on the CVD MoS<sub>2</sub> sample. Mean and standard deviation (SD) values have been calculated, proving that the defectiveness of the sample decreases by increasing the Hg<sup>2+</sup> concentration.



**Fig S2.** Low temperature PL characterization of CVD MoS<sub>2</sub> at different Hg<sup>2+</sup> concentrations. **a)** Pristine CVD MoS<sub>2</sub>. **b)** 1 μM exposed MoS<sub>2</sub>. XB<sub>1</sub> and XB<sub>2</sub> bands' intensity, related to defects, strongly decreased after Hg<sup>2+</sup> exposure, proving again defect healing. Neutral exciton band (X<sup>0</sup>) increase after Hg<sup>2+</sup> exposure. Both A and B exciton bands are blue-shifted. All these observations are in good accordance with the p-type doping observed in the electrical characterization.